L Number	Hits	Search Text	DB	Time stamp
1	98	(((resist or photoresist or	USPAT;	2004/08/14 10:19
		photopolymer\$7) and (((Ar or argon) and	US-PGPUB;	
		(Ne or neon)) with (flow or flowrate or	EPO; JPO;	
1		rate or sccm or slm))) not ((430/328.ccls.	IBM_TDB	
		not 430/313.cor.) and ((Ar or argon or		
		inert) with (flow or flowrate or rate))))		
		not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate		
		or rate))))		
2	3	////	USPAT;	2004/08/14 10:20
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM_TDB	
3	1	cur\$3 or harden\$3))) and etch\$3) and (Ne) (((((resist or photoresist or	HCDAM.	2004/00/14 10 01
		photopolymer\$7) near3 (develop\$3)) with	USPAT; US-PGPUB;	2004/08/14 10:24
ĺ		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM TDB	
		cur\$3 or harden\$3))) and etch\$3) and neon		
4	2	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/08/14 10:25
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		<pre>photoresist or resist))) and (neon same (flow or flowrate))</pre>	IBM_TDB	
5	21	430/313.cor. and 430/328.cxr. not (etch\$3	HODE	0004/00/44
	21	with chamber)	USPAT;	2004/08/14 10:28
		With Grander,	US-PGPUB; EPO; JPO;	
			IBM TDB	
6	17	((((post adj (expos\$ or develop\$4)) adj20	USPAT;	2004/08/14 10:30
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	2001, 00, 11 10:50
		or silicone) with (polymer\$7 or	EPO; JPO;	
		<pre>photopolymer\$7 or photoresist or resist)))</pre>	IBM_TDB	
		not ((silicon or Si) near3 (wafer or		
7	3	<pre>substrate()() and etch\$3 (((ultraviolet or uv) with (neon)) and</pre>	Harra	0004/00/44
'	3	((cross adj link\$3 or cur\$3 or harden\$3)	USPAT;	2004/08/14 10:31
ļ		with (polymer\$7 or photopolymer\$7 or	US-PGPUB; EPO; JPO;	ļ
		photoresist or resist))) and ((Ar or argon	IBM TDB	
		or inert) with (flow or flowrate or rate))		
8	15	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/08/14 10:32
		or argon or inert) with (flow or flowrate	US-PGPUB;	
		or rate))	EPO; JPO;	
9	12	///30/320 colo pot //20/212	IBM_TDB	
	12	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate	USPAT;	2004/08/14 10:32
	İ	or rate))) not ((430/328.ccls. not	US-PGPUB; EPO; JPO;	
		430/313.cor.) and ((Ar or argon or inert)	IBM TDB	
		with (flow or flowrate or rate)))	TD.1_1DD	
10	2	((430/328.ccls. not 430/313.cor.) and	USPAT;	2004/08/14 10:33
		(((Ar or argon) and (Ne or neon)) same	US-PGPUB;	
		(flow or flowrate or rate or sccm or	EPO; JPO;	
		slm))) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert)		
11		<pre>with (flow or flowrate or rate))) ((resist or photoresist or photopolymer\$7)</pre>	HCDAm.	2004/00/14 12 22
-	- 0	and (((Ar or argon) and (Ne or neon)) with	USPAT; US-PGPUB;	2004/08/14 10:33
İ		(flow or flowrate or rate or sccm or slm))	EPO; JPO;	
		same etch\$3) not ((430/328.ccls. not	IBM TDB	
		430/313.cor.) and ((Ar or argon or inert)		
		with (flow or flowrate or rate)))		

12 98	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:34
	_		
13 646	or rate))) (430/328.ccls. not 430/313.cor.) not ((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm))) not (((resist or photopolymer\$7)) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) same etch\$3) not	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:36
	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate		
14 3	or rate))))) (((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:37
15 1		USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:37
16 0	(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:38
17 135	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/08/14 10:38
18 7	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/14 10:39

19	89	((ultraviolet or uv) with (Ne)) and	USPAT;	1 2004 (00 (14 12 00
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	2004/08/14 10:39
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))	IBM TDB	
20	4		USPAT:	2224 /22 /1 : 1 :
	1			2004/08/14 10:40
		"Ten chamber)	US-PGPUB;	
			EPO; JPO;	
21	5	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	IBM_TDB	000440041
			USPAT;	2004/08/14 10:41
			US-PGPUB;	1
			EPO; JPO;	
22	19	430/328.ccls. and (uv or ultraviolet or	IBM_TDB	0004400411
		ultra adj violet) same (temperature or	USPAT;	2004/08/14 10:42
		\$4"degree") same plasma	US-PGPUB;	]
		va degree / Same prasma	EPO; JPO;	
23	156	430/328.ccls. and (uv or ultraviolet or ultra adj violet) same (temperature or \$4"degree") not plasma	IBM_TDB	000010010
20	150		USPAT;	2004/08/14 10:45
İ			US-PGPUB;	
			EPO; JPO;	
24	4.3	1 100/010:0010: did (dv Oi diffaviolef Oi	IBM_TDB	
	15		USPAT;	2004/08/14 11:03
	1	ultra adj violet) same (\$4"degree") same plasma not 430/328.ccls.	US-PGPUB;	
		prasma not 430/328.ccis.	EPO; JPO;	
25	374	(regist or photometal)	IBM_TDB	
23	374	( a compared to procored to c) dame (uv or	USPAT;	2004/08/14 11:04
		ultraviolet or ultra adj violet) same	US-PGPUB;	
	[	(\$4"degree") same plasma	EPO; JPO;	
26	25	250/504R-504H.ccls. and plasma and (uv or ultraviolet or ultra adj violet) same (\$4"degree")	IBM_TDB	
	25		USPAT;	2004/08/14 11:05
			US-PGPUB;	]
			EPO; JPO;	
			IBM TDB	